

## Q. Metrology, Inspection, and Yield Enhancement 분과

2020년 2월 14일(금), 10:45-12:30 / Room H (하트 I, 6층)

### ■ [FH2-Q] Metrology, Inspection, and Yield Enhancement

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<p><b>FH2-Q-1</b> 10:45-11:15</p>	<p>[초청] <b>High-Resolution Inspection System based on Field Emission X-Ray Source for Non-Destructive Testing</b> Jehwang Ryu<sup>1</sup>, Amar Prasad Gupta<sup>1</sup>, Wooseob Kim<sup>1</sup>, Han Gyeol Park<sup>2</sup>, Seung Jun Yeo<sup>2</sup>, Jaekyu Jang<sup>2</sup>, Jaeik Jung<sup>2</sup>, Jung Sun Ahn<sup>1</sup>, and Seung Hoon Kim<sup>3</sup> <sup>1</sup>Kyung Hee University, <sup>2</sup>CAT Beam Tech Co., Ltd., <sup>3</sup>Asan Medical Center</p>
<p><b>FH2-Q-2</b> 11:15-11:45</p>	<p>[초청] <b>MAPS(Multi-axis Absolute Position-posture Sensor) and Smart Stage</b> Jae Wan Kim<sup>1</sup> and Jong-Ahn Kim<sup>2</sup> <sup>1</sup>Batugem Co., Ltd., <sup>2</sup>KRISS</p>
<p><b>FH2-Q-3</b> 11:45-12:00</p>	<p><b>변형거울을 이용한 Standalone TSOM 광학계 개발</b> 유병건, 이대열, 박준성, 이준호 Department of Optical Engineering, Kongju National University</p>
<p><b>FH2-Q-4</b> 12:00-12:15</p>	<p><b>Deep Learning Based Wafer Edge Defect Detection System</b> Gil-Jun Lee<sup>1,2</sup>, Jee-Hyong Lee<sup>3</sup>, and Simon S. Woo<sup>2</sup> <sup>1</sup>MEMC Korea Co., Department of Applied Data Science, Sungkyunkwan University, <sup>2</sup>Department of Applied Data Science, Sungkyunkwan University, <sup>3</sup>Department of Computer Science, Sungkyunkwan University</p>
<p><b>FH2-Q-5</b> 12:15-12:30</p>	<p><b>EUV Ptychography Microscope를 이용한 Through Pellicle 이미징 연구</b> 김영웅<sup>1</sup>, 우동곤<sup>1</sup>, 장용주<sup>2</sup>, 위성주<sup>1</sup>, 안진호<sup>1,2,3</sup> <sup>1</sup>한양대학교 신소재공학과, <sup>2</sup>한양대학교 나노반도체공학과, <sup>3</sup>나노과학기술연구소</p>